

## Supplementary Information

### Nanorod structure tuning and defect engineering of MoO<sub>x</sub> for high performance SERS substrates

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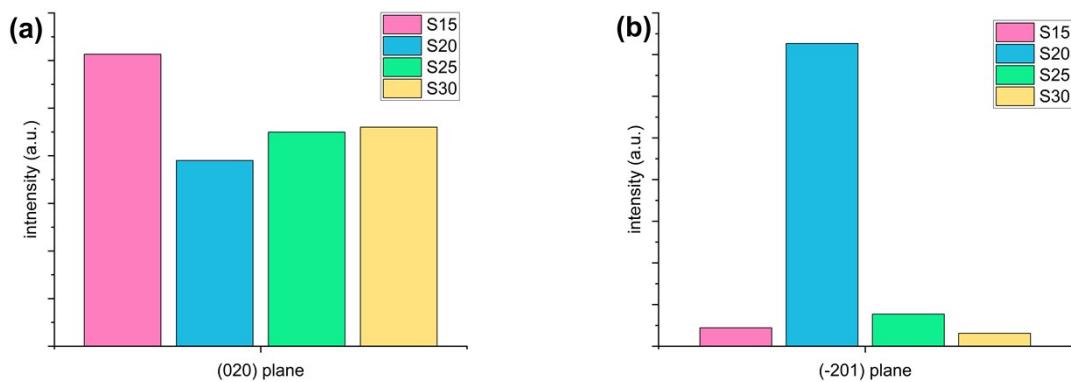
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**Table S1** Fabrication parameters of  $\text{MoO}_x$  rod-like SERS substrate

Sputtering parameter	Parameter value	Unit
Substrate temperature	30	°C
Target-to-substrate distance	7	cm
Base pressure	$1.48 \times 10^{-6}$	Torr
Working gas pressure	$8.35 \times 10^{-3}$	Torr
Power	60	W
Ratio between Ar: O <sub>2</sub> (99.99% purity)	10:2	sccm



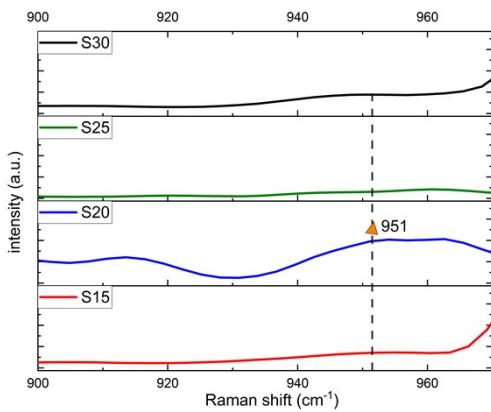
**Fig S1.** Comparison intensity of X-ray diffraction pattern of  $\text{MoO}_x$  thin films deposited at various sputtering time on glass substrate

a) at (020) plane for sample S15, S20, S25, and S30;

b) at (-201) plane for sample S15, S20, S25, and S30.

**Table S2:** Lattice parameters and crystal sizes of samples S15, S20, S25, and S30

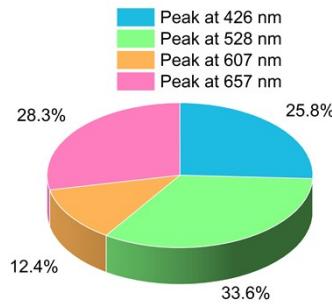
	$\text{MoO}_3$ (standard value) <sup>28</sup>	S15	S20	S25	S30
<b>Lattice parameter</b>					
a ( $\text{\AA}$ )	3.962	3.963	3.970	3.962	3.960
b ( $\text{\AA}$ )	13.858	13.887	13.887	13.891	13.888
c ( $\text{\AA}$ )	3.696	3.698	3.698	3.696	3.698
<b>Crystal size (nm)</b>					
(020)		71.3	77.6	86.0	96.7



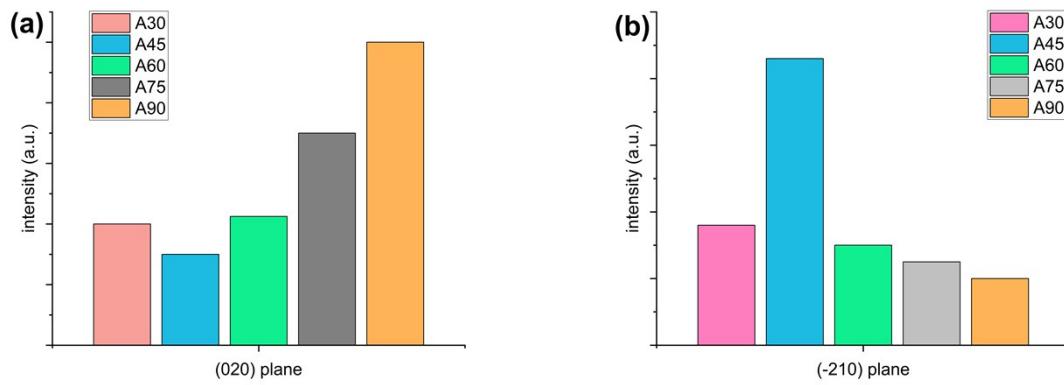
**Fig. S2.** Raman intensity at  $951\text{ cm}^{-1}$  peak for S15, S20, S25, and S30 samples.

**Table S3:** The vibration modes and intensities of characteristic peaks in the Raman spectra for S15, S20, S25, and S30 samples.

Band frequency (cm⁻¹)	Representation <sup>31</sup>	Attribution <sup>31</sup>
115	B <sub>2g</sub>	Translational rigid MoO <sub>4</sub> chain mode along "c" direction T <sub>c</sub>
127	B <sub>3g</sub>	Translational chain mode along "c" direction (T <sub>c</sub> )
158	A <sub>g</sub> /B <sub>1g</sub>	Translational chain mode along "b" direction (T <sub>b</sub> )
198	B <sub>2g</sub>	τ O=M=O twist
216	A <sub>g</sub>	Rotational rigid MoO <sub>4</sub> chain mode R <sub>c</sub>
245	B <sub>3g</sub>	τ O=M=O twist
283	B <sub>2g</sub>	δ O=M=O wagging
337	A <sub>g</sub> , B <sub>1g</sub>	δ O-M-O bend
378	B <sub>1g</sub>	δ O-M-O scissor
473	A <sub>g</sub>	υ <sub>as</sub> O-M-O stretch and bend
663	B <sub>2g</sub> , B <sub>3g</sub>	υ <sub>as</sub> O-M-O stretch
815	A <sub>g</sub>	υ <sub>s</sub> M=O stretch MoO <sub>6</sub>
990	A <sub>g</sub> , B <sub>1g</sub>	υ <sub>as</sub> M=O asymmetric stretch



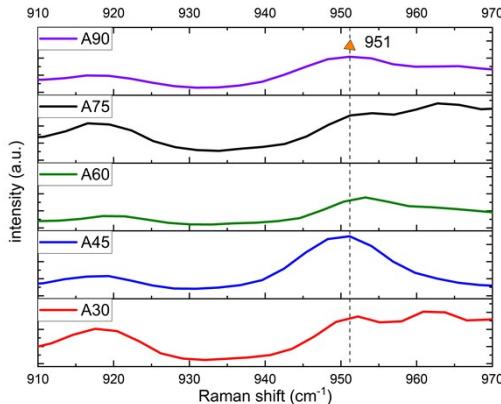
**Fig. S3.** The pie charts illustrate the contribution of component emissions to the total PL spectrum of S20.



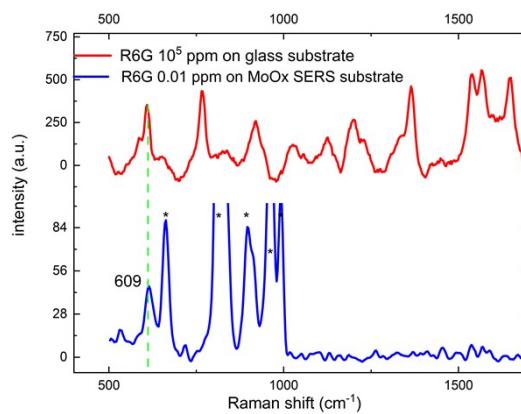
**Fig. S4.** Comparison intensity of X-ray diffraction pattern of  $\text{MoO}_x$  thin films deposited at various annealing time on glass substrate. a) at (020) plane for sample A30, A45, A60, A75, and A90. b) at (-201) plane for sample A30, A45, A60, A75, and A90.

**Table S4:** Lattice parameters and crystal sizes of samples A30, A45, A60, A75, and A90.

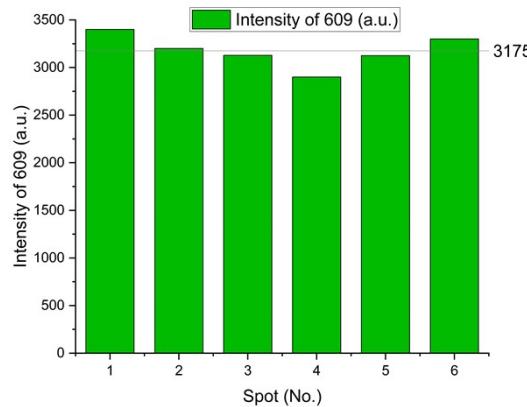
	$\text{MoO}_3$ (standard value) <sup>28</sup>	A30	A45	A60	A75	A90
Lattice parameter (Å)						
a (Å)	3.962	3.970	3.974	3.965	3.963	3.963
b (Å)	13.858			13.885	13.886	13.881
c (Å)		3.696	3.695	3.698	3.700	3.697
Crystal size (nm)						
(020)		77.5	85.5	86.0	85.5	86.0
(110)		43.4	54.1	61.9	61.9	61.9



**Fig. S5.** Raman intensity at  $951\text{ cm}^{-1}$  wavenumber for A30, A45, A60, A75, and A90 samples



**Fig. S6.** Raman spectra of R6G at  $10^5\text{ ppm}$  on glass substrate and  $0.01\text{ ppm}$  onto SERS substrate to calculate EF.



**Fig. S7.** The intensity at  $609\text{ cm}^{-1}$  peak of R6G on six SERS MoO<sub>x</sub> substrates which fabricated under the same condition.

**Table S5:** SERS intensity of R6G at 609 cm<sup>-1</sup> peak absorbing on six MoO<sub>x</sub> SERS substrates which fabricated under the same condition

No.	1	2	3	4	5	6
Intensity (a.u.)	3400	3200	3128	2900	3125	3300
<b>Summary</b>						
Count		Sum		Average	SD	RSD (%)
6		19053		3175.5	171.58526	5.38

**Table S6:** SERS intensity of R6G at 609 cm<sup>-1</sup> peak at five random positions with 1 ppm adsorbed on the surface of MoO<sub>x</sub> SERS substrate produced after 3 months, 6 months, and 9 months.

No.	3 months	6 months	9 months
1	3000	3200	3100
2	3100	2950	3200
3	2800	3257	2500
4	3500	2400	2800
5	3200	2784	2700
<b>Summary</b>			
Sample	count	sum	average
3 months	5	15600	3120
6 months	5	14591	2918
9 months	5	14300	2860
		SD	RSD (%)
		258.84358	8.23
		347.04063	11.89
		482.70074	13.32